

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Wunnicke, et al.

Docket No.:

INF-138

Serial No.:

10/781,920

Art Unit:

1756

Filed:

February 20, 2004

Examiner:

TBD

For:

Method for Fabricating a Resist Mask for Patterning Semiconductor

Substrates

Certificate of Mailing via First Class Mail (37 C.F.R. § 1.8(a))

Date of Deposit:

August 13, 2004

I hereby certify that the below listed correspondence is being deposited with the United States Postal Service on the date indicated above as first class mail in an envelope addressed to: Mail Stop Amendment, Commissioner for Patents, P. O. Box 1450, Alexandria, VA 22313-1450.

Certificate of Mailing via First Class Mail (1 page)
Information Disclosure Statement (1 page)
IDS Combined Form PTO/SB/08a and 08b (1 page) citing (5) references
Copies of (4) cited references
Transmittal of Certified Copy of Priority Document (1 page)
Certified Copy of DE 103 07 523.2
Return Postcard

Respectfully submitted,

Natalië Swider

Natalie Swider

Legal Assistant

Slater & Matsil, L.L.P. 17950 Preston Rd., Suite 1000

Dallas, TX 75252 Tel: 972-732-1001 Fax: 972-732-9218

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Mail Stop: Amendment Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicants wish to bring to the attention of the Patent and Trademark Office the information noted on the enclosed combined form PTO/SB/08a & 08b that may be considered material to the examination of the above-identified application.

No fee is due at this time, as this Information Disclosure Statement is being filed pursuant to 37 C.F.R. § 1.97(b)(3), before the mailing of a first Office action on the merits.

August 13, 2004

Date

Respectfully submitted,

Ira SV Mateil

Attorney for Applicants

Reg. No. 35,272

Slater & Matsil, L.L.P. 17950 Preston Rd., Suite 1000 Dallas, TX 75252 (972) 732-1001 (phone) (972) 732-9218 (fax)



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Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Transmittal of Certified Copy of Priority Document

Dear Sir:

Attached please find a certified copy of the foreign application from which priority is claimed for this case:

Country:

Germany

Application Number: 103 07 523.2

Filing Date:

February 21, 2003

Respectfully submitted,

Reg. No. 35,272

Attorney for Applicants

Slater & Matsil, L.L.P. 17950 Preston Rd., Suite 1000

Dallas, TX 75252 Tel: 972-732-1001 Fax: 972-732-9218

PTO/SB/08a (08-03)

Approved for use through 07/31/2006. OMB 0651-0031
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Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB control number. Complete if Known Substitute for form 1449A/PTO 10/781,920 Application Number INFORMATION DISCLOSURE 2/20/2004 Filing Date STATEMENT BY APPLICANT First Named Inventor Wunnicke, et al. Art Unit 1756 (Use as many sheets as necessary) TBD **Examiner Name**

Attorney Docket Number

INF-138

U.S. PATENT DOCUMENTS						
Examiner Initials*	Cite No.1	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	
		Number - Kind Code ^{2 (if known)}				
	1	US-4,914,006	04-03-1990	Kato, et al.		
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FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No.1	Foreign Patent Document Country Code ³ - Number ⁴ - Kind Code ⁵ (<i>if known</i>)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
	2	WO 02/067304 A1	08-29-2002	Hyon, Man-Sok		
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		NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	3	TANAKA, T., et al., "Mechanism of Resist Pattern Collapse during Development Process," Jpn. J. Appl. Phys. Vol. 32, Part I, No. 12B, December 1993, pp. 6059-6064.	6
	4	CAO, H.B., et al., "Comparison of Resist Collapse Properties for Deep Ultraviolet and 193 nm Resist Platforms," J. Vac. Sci. Technol. B, Vol. 18, No. 6, Nov/Dec 2000, pp. 3303-3307.	
***************************************	5	DÖRFLER, HD, "Grenzflächen und Kolloidchemie," VCH, 1994, ISBN 3-527-29072-9, pp. 225-229	

Examiner	Date	
Signature	Considered	

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. ¹Applicant's unique citation designation number (optional). ²See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶Applicant is to place a check mark here if English language Translation is attached.

Translation is attached.

This collection of information is required by 37 CFR 1.97 and 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.